METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST

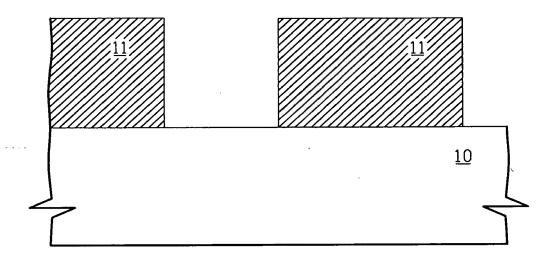


FIG.1A(Prior Art)

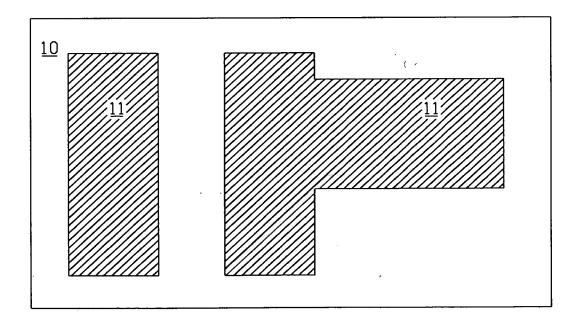


FIG.1B(Prior Art)

METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST



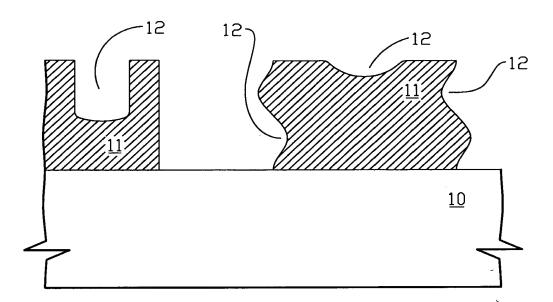


FIG.1C(Prior Art)

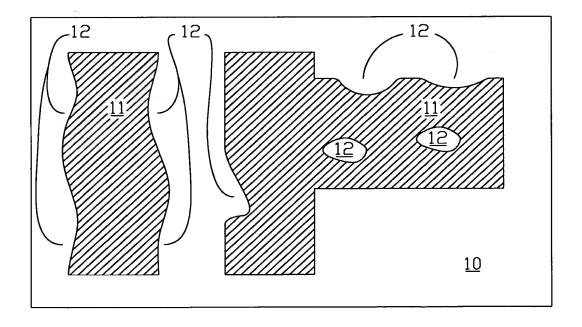


FIG.1D(Prior Art)

METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST Application No. 09/919,868



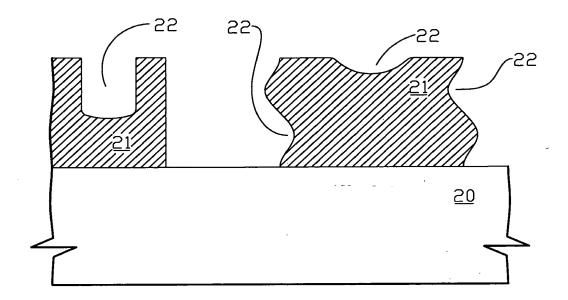


FIG.2A

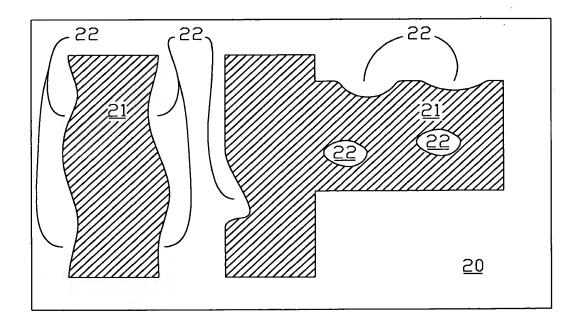
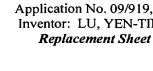


FIG.2B

METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST Application No. 09/919,868 Inventor: LU, YEN-TING



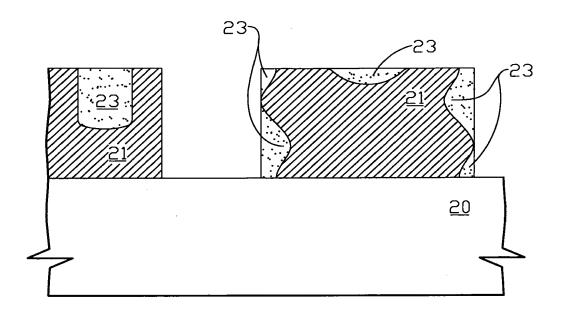


FIG.2C

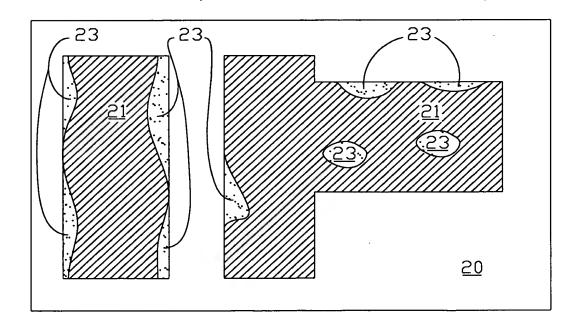


FIG.2D

METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST



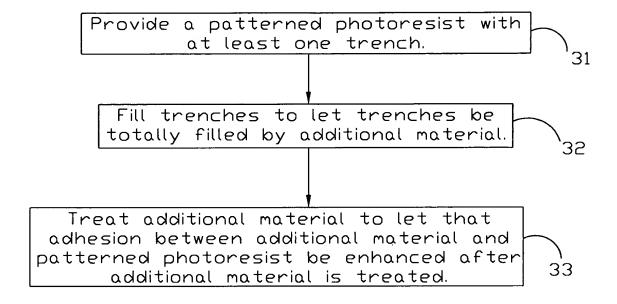


FIG.3A

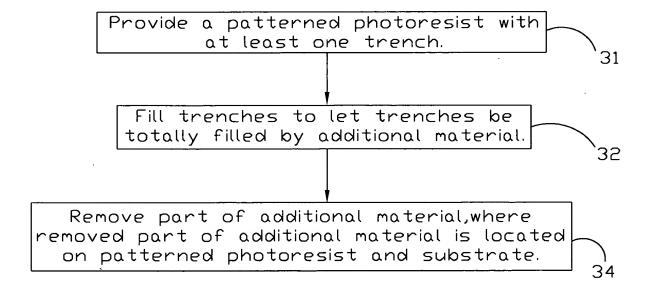


FIG.3B

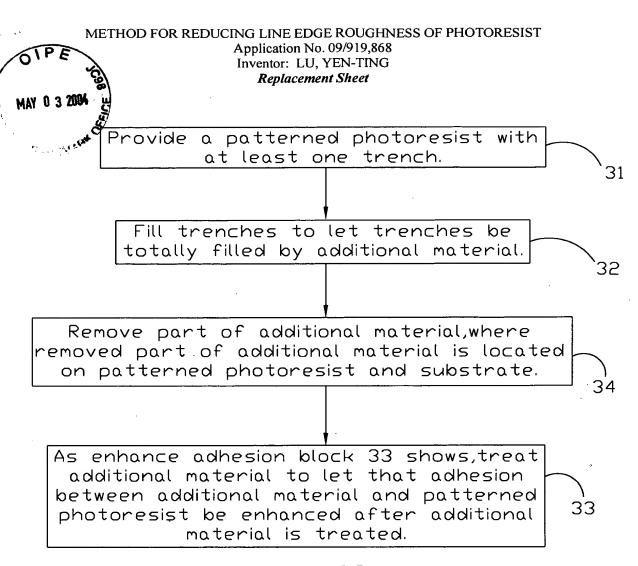


FIG.3C